



ATTORNEYS AT LAW

Docket No.: 263788US2PCT

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313

RE: Application Serial No.: 10/519,475
Applicants: Keisuke KAWAMURA, et al.
Filing Date: December 28, 2004
For: APPARATUS FOR PLASMA PROCESSING,
METHOD OF PROCESSING SUBSTRATE
THEREWITH, APPARATUS FOR PLASMA-
ENHANCED CHEMICAL VAPOR DEPOSITION,
AND METHOD FOR FILM FORMATION
THEREWITH
Group Art Unit: 1763
Examiner: ARANCIBIA, M. G.

SIR:

Attached hereto for filing are the following papers:

ELECTION

Our online credit card payment in the amount of **\$0.00** is being made covering any required fees. In the event any variance exists between the amount enclosed and the Patent Office charges for filing the above-noted documents, including any fees required under 37 C.F.R. 1.136 for any necessary Extension of Time to make the filing of the attached documents timely, please charge or credit the difference to our Deposit Account No. 15-0030. Further, if these papers are not considered timely filed, then a petition is hereby made under 37 C.F.R. 1.136 for the necessary extension of time.

Respectfully submitted,

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